

1

2

## Abstract of the Disclosure

3

4 The invention relates to an exposure apparatus, in particular for wavelength-  
5 dependent light outcoupling, in which at least one preferably wavelength-  
6 dependent mirror layer is located within an exposure beam path of a lamp, which  
7 mirror layer is used to divide the beam path into a spectral portion used for  
8 exposure, and into an unused spectral portion. The object of the invention is to  
9 provide an exposure apparatus and a method with which the quality of exposure  
10 can be optimized using simple means. The object on which the invention is  
11 based is attained according to the invention by locating a mirror in the beam path  
12 of the unused region of the spectrum that reflects the unused spectral range in  
13 the direction of a mirror layer, and a portion of this is projected onto a viewing  
14 screen for adjustment purposes.